

In the Specification:

Please make the following changes in the specification paragraphs and sections designated by page and line number:

Page 5, lines 16 to 30 (Brief Description of the Drawing section):

Brief Description of the Drawing Drawings

Figure 1 is a schematic cross-sectional view of a cross-section of an embodiment of the substrate according to the invention embodied ~~applied~~ as a mirror for EUV microlithography[[:]].

Figure 2 is a schematic cross-sectional view of a cross-section of an embodiment of the substrate according to the invention embodied as ~~applied in a~~ mask blank for EUV microlithography[[:]].

Figure 3 is a schematic cross-sectional view of a cross-section of an embodiment of the substrate according to the invention embodied as ~~applied in a~~ mask for EUV microlithography[[:]].

Page 6, lines 4 to 14:

According to the invention, it has been found that the ~~above-described drawback~~ of disadvantages of the above-described materials, such as the glass-ceramics and/or ceramics, can surprisingly be eliminated by the application of a covering layer with a low thermal expansion, comprising, for example, silicon dioxide, to a

lower layer, comprising a material with a very low thermal expansion, such as a glass-ceramic. In particular, this base layer may have poor ~~a worse~~ surface roughness and yet it is still possible to provide ~~establish~~ the surface roughness, which is required for microlithography, by means of the covering layer.

Page 8, lines 9 to 19:

Zerodur® was first described in DE 19 02 432. Zerodur® M is a Zerodur® composition which is substantially free of magnesium oxide and is described, for example, in US 4,851,372. Properties and composition of Zerodur® and Zerodur® M are known ~~new~~ from the prior art and have been described, for example, in "Low Expansion Glass Ceramics", H. Bach (editor), Schott Series on Glass and Glass Ceramics, Science Tehnology, and Applications, Springer Verlag, Germany. The cited publications relating to Zerodur® and similar glass-ceramics are herein incorporated by reference.

Page 19, lines 28 to 30:

The method for the production of the substrate for precision components is ~~are~~ the same as described above for the substrate for EUV microlithography.